## Metal/2D Solid/Si study for spintronic application

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The Spin-FET concept by Datta-Das, inaugurated years of research for spin injection into semi-conductor [1]. As shown by Fert and Jaffrès the control of tunnel contact resistance is the key point to obtain an efficient electrical spin injection from ferromagnetic metal into semi-conductor [2]. This control is hardly obtained with conventional oxides, due to the formation of defect states during oxide deposition [3]. The use of 2D atomic crystals (graphene, h-BN...) seems to be a promising way to avoid surface defects formation and control interface resistance.

We studied by x-ray photoemission spectroscopy and electrical (I(∨) characterisation and C(V)the electronic properties of metal/2D solid/ Silicon interface. By these methods we have shown that adding graphene at the interface induces a high reduction of barrier height compared Schottky to Metal/Silicon intimate contacts [figure1]. This ohmic-like behaviour is detrimental for electrical spin injection and detection [figure 2].

In addition to iron we studied the electronic transport properties of Au/2D Solid/n-Si and showed a similar behaviour. This results is of particular interest for the realisation of ohmic contact onto Si. References

- S. Datta and B. Das Appl. Phys. Lett. 56, 665 (1990)
- [2] A. Fert and H. Jaffrès, Phys. Rev. B **64**,1 (2001)

[3] J.-C Le Breton et al, Appl. Phys. Lett **91**, 172122 (2007)

Figures



**Figure 1:** Schottcky barrier height as a function of iron thickness. These measurements have been realized with silicon doping at 10<sup>16</sup> cm<sup>-3</sup>.



**Figure 2:** Current as a function of applied voltage with (red) and without (black) graphene at interface.